

**REMARKS**

The Examiner's Action mailed on September 20, 2005 has been received and its contents carefully considered. In this Amendment, Applicants have amended certain claims, and also editorially amended the specification during review of the application. Specifically, the present amendment has amended claims 1, 9 and 10, and has canceled claims 11 and 12. Claims 1 and 8 are independent claims. After entry of the above-amendments, claims 1-10 remain pending in the application. For at least the following reasons, it is submitted that this application is in condition for allowance.

Claims 1-10 were tentatively rejected under 35 U.S.C. § 102(b) as allegedly anticipated by *Dohjo et al. (Dohjo)* (U.S. Patent No. 6,078,366). For at least the following reasons, Applicants respectfully disagree and request reconsideration and withdrawal of the rejections.

It is well settled that a reference may anticipate a claim within the purview of 35 USC §102 only if all the features and all the relationships recited in the claim are taught by the reference either by clear disclosure or under the principle of inherency.

However, the cited reference does not disclose various features recited in independent claims 1 and 8.

First, Applicant's amended independent claim 1 recites a manufacturing method of a **transflective** TFT-LCD panel. In this method, a first conductive layer is formed on a substrate, and the first conductive layer is then patterned to form a gate. A dielectric layer is formed on the substrate to cover the gate, and a channel is formed on the dielectric layer and disposed over the gate. Then, a **photo-resist block** is formed, and a second conductive layer is formed to cover the channel and the photo-resist block. Next, the second conductive layer is patterned to form a source, a drain and a photo-reflective layer, wherein the source and the drain are disposed above the gate, and the photo-reflective layer is formed on the photo-resist block.

After the second conductive layer is patterned, a protection layer is formed to cover the source, the drain and the photo-reflective layer. Then, the protection layer is patterned to form a first opening on the drain allowing part of the drain to be exposed, and a second opening on the photo-reflective layer allowing part of the photo-reflective layer to be exposed. At last, a transparent electrode is formed to electrically connect to the drain and the photo-reflective layer via the first opening and the second opening.

In contrast, *Dohjo* discloses a method of manufacturing an optical **transmissive** LCD (Col. 16, lines 48-50), and the method comprises seven process steps. In the first process step, the scanning lines (111) are formed on a glass substrate (101) (Col. 19, lines 28-40 & FIG. 20). In the second process step, a first gate insulator film (115), a second gate insulator film (117), a semiconductor coated film (119) and a channel protective coated film (121) are formed (Col. 19, lines 43-55 & FIG. 21). In the third process step, the coated film (121) is patterned to form a channel protective film (122) (Col. 19, lines 58-67 & FIG. 22). In the fourth process step, a coated film (123) made of  $n^+$  a-Si is deposited on the coated film (119), and a Mo-W alloy film (125) is deposited on the coated film (123) (Col. 20, lines 8-13 & FIG. 23). In the fifth process step, the Mo-W alloy film (125) and the  $n^+$  a-Si coated film (123) are patterned to form the drain electrode (126a), the source electrode (126b), the light shield layer (170), and the low-resistance  $n^+$  a-Si films (124a) and (124b). (Col. 20, lines 22-40 & FIG. 24). It should be noted that the light shield layer (170) is made of Mo-W alloy (Col. 20, lines 38-39), and the low-resistance semiconductor film (124b) is made of  $n^+$  type doped amorphous silicon ( $n^+$  a-Si). In the sixth process step, a dielectric film (127) and a contact hole (129a) are formed (Col. 20, lines 43-50 & FIG. 25). In the seventh process step, a pixel electrode (131) is formed (Col. 20, lines 60-65 & FIG. 26).

Section 4 of the Office Action alleges that *Dohjo* has “a photo-resist block (170), and a photo-reflective layer (124b)”. However, the light shield layer (170) is made of Mo-W alloy and the film (124b) is made of n+ a-Si. In contrast to the position of the Office Action, *Dohjo* fails to disclose (or even to suggest) the photo-resist block and the photo-reflective layer (225, made of metal), as the present invention discloses. Besides, *Dohjo* fails to disclose (or even to suggest) a manufacturing method of a **transflective** TFT-LCD panel. Instead, *Dohjo* discloses a method of manufacturing an optical **transmissive** LCD. Moreover, there is no disclosure (or even a suggestion) from *Dohjo* that the second conductive layer is patterned to form a source, a drain and a photo-reflective layer simultaneously, wherein the source and the drain are disposed above the gate, and the photo-reflective layer is formed on the photo-resist block, as recited in claim 1. As such, it is submitted that Applicant’s independent claim 1, as well as the claims 2-7 dependent therefrom, are not anticipated by (or rendered obvious by) the cited reference.

With regard to independent claim 8, Applicant’s independent claim 8 recites a manufacturing method of a **transflective** TFT-LCD panel equipped with a transmissive area and a reflective area. The method comprises the steps of: forming a thin film transistor and a capacitor electrode on the substrate, wherein a photo-reflective layer within the reflective area and a source and a drain of the thin film transistor are formed simultaneously; and forming a transparent electrode within the transmissive area. In contrast, there is no disclosure (or even a suggestion) from *Dohjo* that a photo-reflective layer is formed within the reflective area. Furthermore, *Dohjo* fails to disclose (or suggest) the step of forming a source, a drain and a photo-reflective layer simultaneously, as recited in claim 8. As such, it is submitted that Applicant’s independent claim 8, as well as the claims 9-10 dependent therefrom, are not anticipated by (or rendered obvious by) the cited reference. It is therefore submitted that this rejection should be withdrawn.


### CONCLUSION

For at least the foregoing reasons, it is submitted that this application is in condition for allowance and such a Notice, with allowed claims 1-10 earnestly is solicited.

If the Examiner believes that a conference would be of value in expediting the prosecution of this application, the Examiner is hereby invited to telephone the undersigned counsel to arrange for such a conference.

No fee is believed to be due in connection with this amendment and response to Office Action. If, however, any fee is believed to be due, you are hereby authorized to charge any such fee to deposit account No. 20-0778.

Respectfully submitted,

By:   
Daniel R. McClure  
Registration No. 38,962

**Thomas, Kayden, Horstemeyer & Risley, LLP**  
100 Galleria Pkwy, NW  
Suite 1750  
Atlanta, GA 30339  
770-933-9500